

ABSTRACT

Provided is an apparatus for treating perfluorinated compound gas used in semiconductor or display manufacturing process. The apparatus includes a first structure which forms a first space, introduces and preheats to-be-treated gas, and discharges treated gas to the outside, a second structure which forms a second space, heats and treats the preheated to-be-treated gas from the first structure, and generates treated gas, a first connector for delivering the preheated to-be-treated gas from the first structure to the second structure and a second connector for delivering the treated gas from the second structure to the first structure, and the first structure includes a heat exchanger for preheating to-be-treated gas with the treated gas, and the second structure includes a heater for heating the preheated to-be-treated gas and a catalyst unit for treating the heated to-be-treated gas.

FIG. 1